

<b>Notice of References Cited</b>	Application/Control No. 10/773,592	Applicant(s)/Patent Under Reexamination CHI HONG PAI	
	Examiner Jasmine J. Clark	Art Unit 2815	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,344,413 B1	02-2002	Zurcher et al.	438/678
	B	US-6,451,688 B1	09-2002	Shimpuku, Fumihiko	438/624
	C	US-6,436,787 B1	08-2002	Shih et al.	438/396
	D	US-6,524,962 B2	02-2003	Chen et al.	438/694
	E	US-6,313,028 B2	11-2001	Huang et al.	438/637
	F	US-6,696,360 B2	02-2004	Ahn et al.	438/632
	G	US-2002/0102834 A1	08-2002	Yang, Tien-Chu	438/618
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	2000-208745	07-2000	JP	Chun-Yun et al.	Ho1L 027/108
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	"Current Technical Trends: Dual Damascene & Low-K Dielectrics, Pages 1-6, Jerry Healey, 2002.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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